

ABSTRACT

There can be provided a method for producing a pattern film-coated article which has excellent film formability, 5 can remove unexposed portions of a film completely in the development step after exposing the film to light, and has excellent pattern accuracy; and a photosensitive composition.

The method for producing a pattern film-coated article
10 comprises the steps of coating a photosensitive composition comprising an organometallic or organosilicon compound having photosensitivity and a hydrolyzable metal or silicon alkoxide on a substrate, irradiating the coated film on the substrate with light to polymerize the exposed portions of
15 the coated film and then dissolving unexposed portions to remove them, wherein a pattern film-coated article is produced from an allyl group-containing metal or silicon alkoxide as the organometallic or organosilicon compound.

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